ANNEALSYS

DLI-CVD / DLI-ALD

APPLICATIONS: Oxides, nitrides, metals and alloys, 2D & 3D materials, etc

Multi-process capabilities inside the same process chamber: CVD, ALD, MOCVD, pulse pressure CVD, RTP & RTCVD

Our DLI-CVD / DLI-ALD machines are equipped with **direct liquid injection vaporizers** for the utilization of the widest range of chemicals including low vapor pressure and thermally unstable precursors.

Annealsys product lines process substrates for silicon, compound semiconductors, nanotechnologies, MEMS, solar cells, glass, etc.

Our process engineers have experience in processing a wide range of substrates: silicon, gallium arsenide, silicon carbide, sapphire, metal, glass, and polymers. The unique features of our machines allows development of new materials.

ABOUT ANNEALSYS

Annealsys Rapid Thermal Processing (RTP) and Chemical Vapor Deposition (CVD/ALD) systems are the best thermal processing solutions for research & development laboratories and small-scale production facilities.

Headquartered out of Montpellier, France, we provide outstanding technical and process customer support through a global sales and service network.

MC-050

2-inch DLI-CVD / DLI-ALD System
Multi-process: CVD, ALD, RTP,...

• Up to 4 direct liquid injection vaporizers
• From room temperature up to 1100°C
• In-situ annealing capability (RTP)
• Multi-process system: CVD, ALD, RTP,...
• Up to 8 process gas lines with MFC
• Optional glovebox interface

MC-100

100mm DLI-CVD / DLI-ALD System
Low cost of ownership

• Up to 3 direct liquid injection vaporizers
• From room temperature up to 800°C
• Multi-process system: CVD, ALD,...
• Rotating and heating substrate holder
• Up to 8 process gas lines with MFC
• Optional motorized loadlock

MC-200

200mm DLI-CVD / DLI-ALD System
Optional capacitance plasma

• Up to 4 direct liquid injection vaporizers
• From room temperature up to 800°C
• Multi-process system: CVD, ALD,...
• Rotating and heating substrate holder
• Up to 8 process gas lines with MFC
• Optional motorized loadlock